THE ANISOTROPY AND SIGN CHANGE OF MAGNETORESISTANCE IN THE LAYERED QUASI ONE-DIMENSIONAL SEMICONDUCTOR TiS₃

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Crystal structure of TiS₃

Transition metal trichalcogenides of Group IV metals. MX_3 , where M =Ti, Zr, Hf; and X=S, Se, Te, are layered quasi one-dimensional compounds. MX_3 are diamagnetic semiconductors. **ZrTe₃** and **TiS₃** show metallic properties. $ZrTe_3$ undergoes a phase transition at 63 K due to CDW formation.



F.S. Khumalo and H.P. Hughes, Phys.Rev.B, **22** 2078 (1980)



E. Guilmeau et.al., Chem. Mater., 26 5585 (2014)

Unit cell parameters: *a*=0.50 nm, *b*=0.34 nm, *c*=0.88 nm. β =98,4° Structural type – monoclinic. Space group – P21/m

Samples











 $^{100\mu m}$ The TiS₃ whiskers with electrical contacts. The current flows along *a*- axis (a), *b*- axis (b), *c*- axis (c)





The diffraction patterns of the TiS_3 whisker at 285 K HVEM JEM-1000



 TiS_3 whisker (the gray stripe in the middle) with 8 Au contacts prepared for R_{xy} and R_{xx} measurements.



The temperature dependencies of the contact resistance to TiS_3 whiskers. Contact resistance at 300 K was ~ 10⁻⁶ Ohm x cm².

The anisotropy of conductivity of TiS₃ whiskers.



The temperature dependences of the resistance of TiS_3 , measured along the **a**, **b**, and **c** axes



The temperature dependences of the logarithmic derivatives dln R/d(1/T) along the *a*, *b*, and *c* axes.



Temperature dependencies of the ratio ρ_a/ρ_b and ρ_c/ρ_b . $\rho_a/\rho_b \sim 5$; $\rho_c/\rho_b \sim 20$ at 300 K. $\rho_c.\rho_a.\rho_b \sim 10^6$:10³:1 at *T*=50 K.

I.G. Gorlova S.G. Zybtsev and V.Ya. Pokrovskii, JETP Lett. **100** 256 (2014).

Power-law behavior of conductivity in TiS₃ whiskers. $I \propto V^{\alpha(T)}$



log *I*-log *V* curves measured along *b*-axis at *T* =4.2, 5.2, 5.6, 6.4, 7.7, 12.8, 24.7, 26.6, 41.5, 58.9, 77.6 K. Inset: *R*(*T*) of the whiskers. ρ_b (300 K) = 0.2 Ohm x cm.



log *I*-log *V* curves measured along *c*-axis at *T* =4.2, 10, 20, 30, 40, 50, 60, 70, 80, 90 K

Hall effect and magnetic susceptibility for TiS₃



The temperature dependence of the Hall resistance for TiS₃. Inset: temperature dependence of the Hall mobility. Electron density: n_{300} , ~10¹⁸ cm⁻³, n_{50} ~10¹⁵ cm⁻³. Electron density per elementary conducting layer at 300 K is ~10¹¹cm⁻², at 50 K - ~ 5×10⁸ cm⁻²



The temperature dependencies of the Hall resistance R_{xy} (*B*=9 T) and *b*-axis resistance R_{xx} for the same whisker. The activation energy: for R_{xx} = 415 K, for R_{xy} = 469 K



The temperature dependences of the magnetic susceptibility of TiS_3 along the *a*, *b*, and *c* axes.



Magnetic field dependencies of *b*-axis resistance R_{xx}



out-of plane fields, $\boldsymbol{B}||c(\bullet)$, in-plane fields, $\boldsymbol{B}||\boldsymbol{I}||b(\bullet)$.



0.95 L

5

H (Oe)

10

x 10⁴

10

x 10⁴

H (Öe)

5

7 د 0

2

4

H (Oe)

6

8

10

x 10⁴



Angle dependences of magnetoresistance of TiS₃





 $H = 4 \times 10^4 \text{ Oe}, I || b$

The temperature dependences of the magnetoresistance of TiS₃, for the magnetic fields *B* directed along the three crystallographic axes.



The transverse magnetoresistance (H||c) as a sum of linear negative and quadratic positive contributions $\Delta R/R = aH^2 + bH$.



At *H* corresponding to the minimum of *R*: $\hbar\omega_c \approx kT$ $(\hbar\omega_c \equiv eH/m_e)$



 $\Delta R/R = \mu^2 H^2$

 $a=10^{\circ} \sim \mu=400 \text{ cm}^2/\text{Vs}$ $a=10^{-2} \sim \mu=40 \text{ cm}^2/\text{Vs}$

Possible mechanisms of magnetoresistance in TiS₃

Negative MR in transverse (out-of plane) fields, *B*||*c*

is observed in layered conductors with charge or antiferromagnetic ordering and is explained by localization induced by defects of different kind. E.g.:

(DMtTSF)₂X, X= BF₄, ClO₄, ReO₄. AF ordering. 2D weak localization induced by disorder in the anion lattice. *J. P. Ulmet et al.*, *Phys. Rev. B* **38** 7782 (1988).

α-(BEDT-TTF)₂**I**₃. Ferroelectric CO phase transition. 2D weak localization induced by disorder in I layers. *T. lvek et al., PRB 96 (2017) 075141*

o-TaS₃ CDW. Delocalization of quantum interference of CDW loop formed in domain structure. *Katsuhiko Inagaki et al., Phys. Rev. B* 93, 075423 (2016)

Positive MR in parallel (in-plane) fields, B||I||b, B||a

is observed in 2D interacting low-density carrier (n~10¹¹ cm⁻²) electron systems, 2D EG. **Si-MOS structures**.

Explanations: Zeeman spin-splitting. V. T. Dolgopolov and A. V. Gold, JETP Lett. **71**, 27 (2000).

Both the spin and Coulomb interaction effects V. M. Pudalov et al., JETP Lett. 65, 932 (1997)

The two parallel dissipation channels : scattering of the electrons by impurities in 2D Fermi liquid and Coulomb scattering of electrons by the collective localized states (spin droplets). *L. A. Morgun et al., Phys.Rev.B* **93**, 235145 (2016)

Intermediate phase between the Fermi-liquid and the Wigner crystal phases. B. Spivak, Phys. Rev. B 67, 125205 (2003)

CONCLUSIONS

The magnetoresistance of whiskers of q-1D layered semiconductor TiS_3 was studied for current flowing along the metal chains (*I* ||*b*) and for the magnetic field *B* directed along the three crystallographic axes: (*B*||*a*), (*B*||*b*), (*B*||*c*), 0<*B*<9 T.

Angular dependences of magnetoresistance reveal quasi 2D nature of the electronic system for T < 100 K.

Anomalous behavior of R(H) below $T_0 \approx 50$ K is observed. A negative transverse (B||c) and positive longitudinal (B||b||I) magnetoresistance has been found.

The results indicate charge- or magnetic-ordering phase transition in 2D layers.